PATENT APPLICATION

THE THE ENGLISH

4/15/02

In re application of

Kuniaki YAGI, et al.

Appln. No.: Not Yet Assigned

Confirmation No.: Not Yet Assigned

Group Art Unit: Not Yet Assigned

Filed: January 18, 2002

Examiner: Not Yet Assigned

For: SINGLE CRYSTAL SIC AND METHOD OF PRODUCING THE SAME AS WELL AS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

SIC SEMICONDUCTOR DEVICE AND SIC COMPOSITE MATERIAL

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please enter the following amended claims:

6. A single crystal SiC, wherein:

the single crystal SiC is obtained by a method claim 1, and

the planar defect density of a top nost surface falls within a range not higher than 10³/cm⁻².

7. A single crystal SiC, comprising:

single crystal SiC obtained by a method chaimed in claim 1, and

another SiC deposited on the single crystal SiC by the vapor phase growth method or the

liquid phase growth method.

10. A SiC composite material, comprising:

single crystal SiC produced by a method claimed in claim 1, and

diamond or GaN formed on the single crystal SiC.

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SOSUSTO CILACE